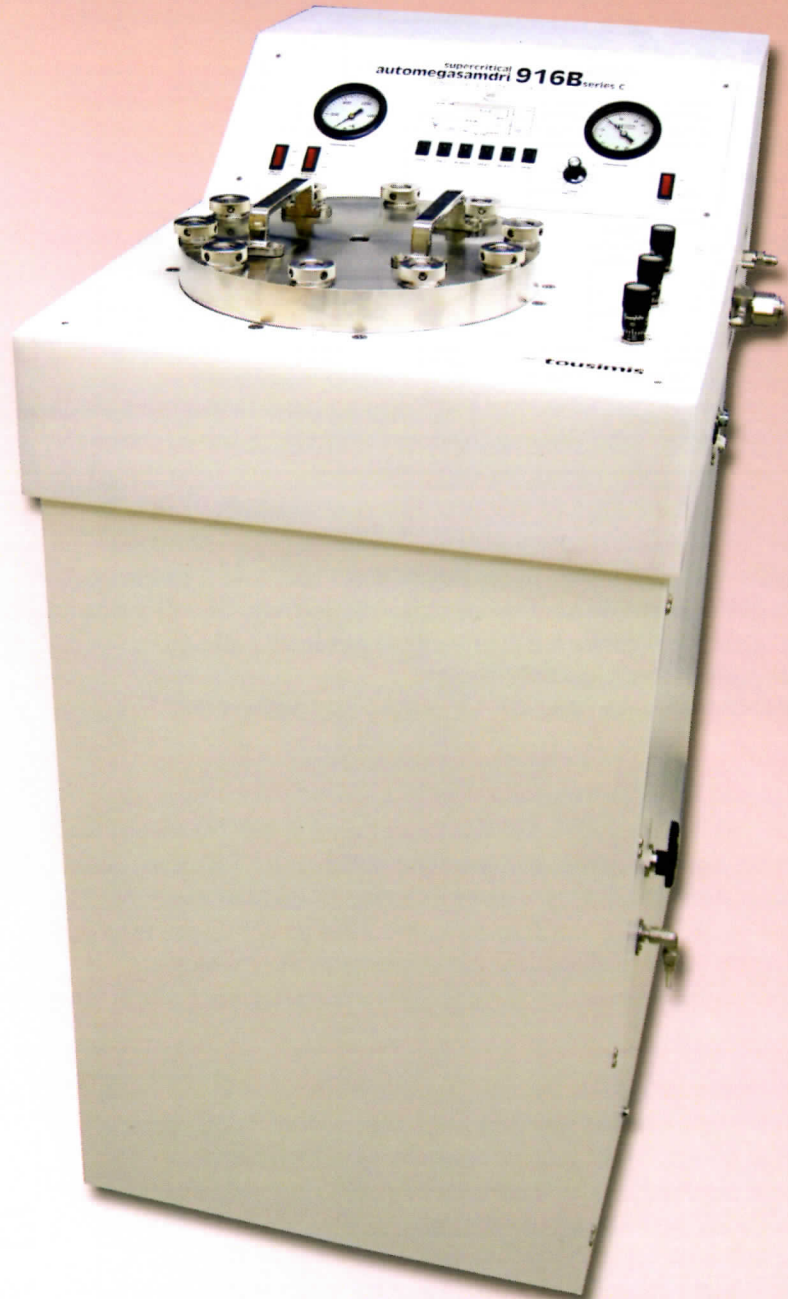


NEW

SUPERCritical CPD MEMS DRYER FOR 8" WAFERS **AUTOMEGASAMDRI®-916B, SERIES C**

UNPARALLELED VERSATILITY AND LOW LCO₂ CONSUMPTION



tousimis

輸入販売元



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- The New Supercritical Automegasamdri®-916B, Series C System was developed by Dr. A. J. Tousimis and our team of long-standing associates within the tousimis® SAMDRI design group.
- Smooth operation and precise control are the Supercritical Automegasamdri®-916B's trademark; wafer holders and inserts are provided that allow flexible CPD processing of 8", 6", 4", 3", 2" wafers as well as 10mm square die.



SUPERCRITICAL Automegasamdri[®]-916B, Series C Catalog# 8786D (Process Various Wafer Sizes up to 8in)

- 40% Less LCO₂ Consumption.¹
- Process up to 5 wafers in Less than 1 hour.
- All inclusive Small Foot Print design.
- Minimal installation Site Preparation required.
- On Site Start-Up and User Training included.²

FEATURES

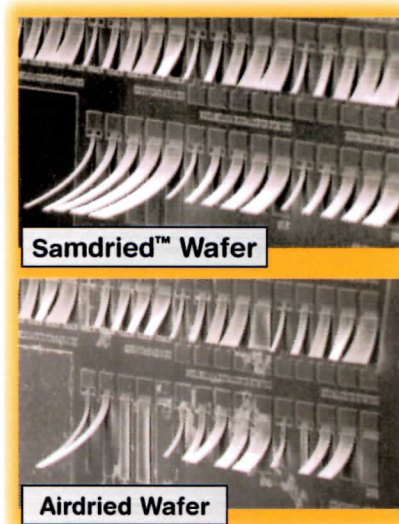
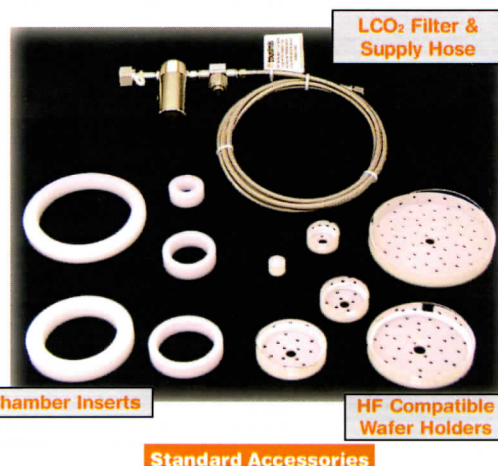
- High efficiency internal closed loop refrigeration.* (22°C to operational in less than 5 minutes)!
- Post-Purge-Filter easily accessible for maintenance ease.*
- The patented internal SOTER™ condenser* quietly captures and separates CO₂ exhaust and waste alcohols.
- Unique chamber inserts* enable variance of chamber I.D. maximizing efficiency in LCO₂ consumption, process time, and providing multiple size wafer process capability!
- Process up to 5 x 8" wafers per process run. Also comes with additional HF Compatible Wafer Holders* to process 5 x 6", 5 x 4", 5 x 3", 5 x 2" diameter wafers or 5 x 10mm square die (tousimis[®] HF compatible Wafer Holders* may be used to etch and process your wafers minimizing handling).
- Chamber illumination with viewing window facilitates chamber status visualization.*
- Microprocessor controller allows for completely automatic processing.*
- All internal surfaces are inert to CO₂ and ultrapure alcohols.
- Repeatable operating parameters insuring "reproducibility" of results.
- Static pressure control module helps insure automatic safe pressure stability.
- Internal filtration system delivers clean LCO₂ into process chamber down to 0.4µm.
- Control panel LED's instantly indicate process mode at a glance.
- Clean room static-free compatible design.
- All electronic components meet CE, UL and/or U.S. Military Specifications.

SPECIFICATIONS

- Cabinet: 21" (53.3cm) Width x 34" (86.4cm) Depth x 45" (114.3cm) Height
- System Set-Up Area Footprint: 27" (68.6cm) Width x 38" (96.5cm) Depth
- Chamber size: 8.50" I.D. x 1.25" Depth / Chamber volume: 1162 ml
- Temperature gauge range: -30°C to 60°C, Pressure gauge range: 0 to 2,000 psi
- 120V / 50-60Hz (Other voltage units also available. Please Inquire)
- LCO₂ flow is precisely controlled through Micro Metering Valves with Vernier handles for adjustment ease.*

STANDARD ACCESSORIES

- LCO₂ High Pressure braided stainless steel inert Teflon[®] lined hose. 10ft (~ 3m) long for clean room operation (at a nominal charge, other lengths available upon request).
- LCO₂ external combination filter assembly (#8784) for water/oil/particulates (down to 0.5µm) pre-installed onto the chamber LCO₂ supply high-pressure hose.
- Tool set included for connecting LCO₂ chamber supply line
- Static free exhaust tubing for all exhaust outlets.
- Internal stainless and nickel scintered filtration systems incorporated to protect lines, wafers, and valves down to 0.4µm.
- Spare chamber O-rings (3), chamber lamps (2), and slo-blow fuses (2x3A and 2x8A).
- Complete wafer size process flexibility! 5 chamber inserts* enable 8.5" chamber I.D. reduction down to smaller chamber I.D. sizes for processing wafers and die from a range including: 8", 6", 4", 3", 2", and 1.25" ! Allows for multiple wafer size drying.
- 8", 6", 4", 3", 2" diameter wafer holders and 10mm square die holders included. Holders are HF compatible and can hold up to 5 wafers or die each.
- 2 year warranty on all parts and labor. Free lifetime technical support consultations by our scientific staff.



¹ Compared with tousimis Automegasamdri[®]-916B, Series B

² Available for most countries. Contact tousimis for details.

* Most Automegasamdri[®] feature U.S. patents (#6,493,964, #6,678,968) or patents pending.

Note: Actual delivered model or accessories may vary slightly, as advancements are being constantly applied.